

Microstructure and Local Charge Distribution in Hydrogenated Nanocrystalline Silicon under Illumination Studied by Electrostatic Force Microscopy.

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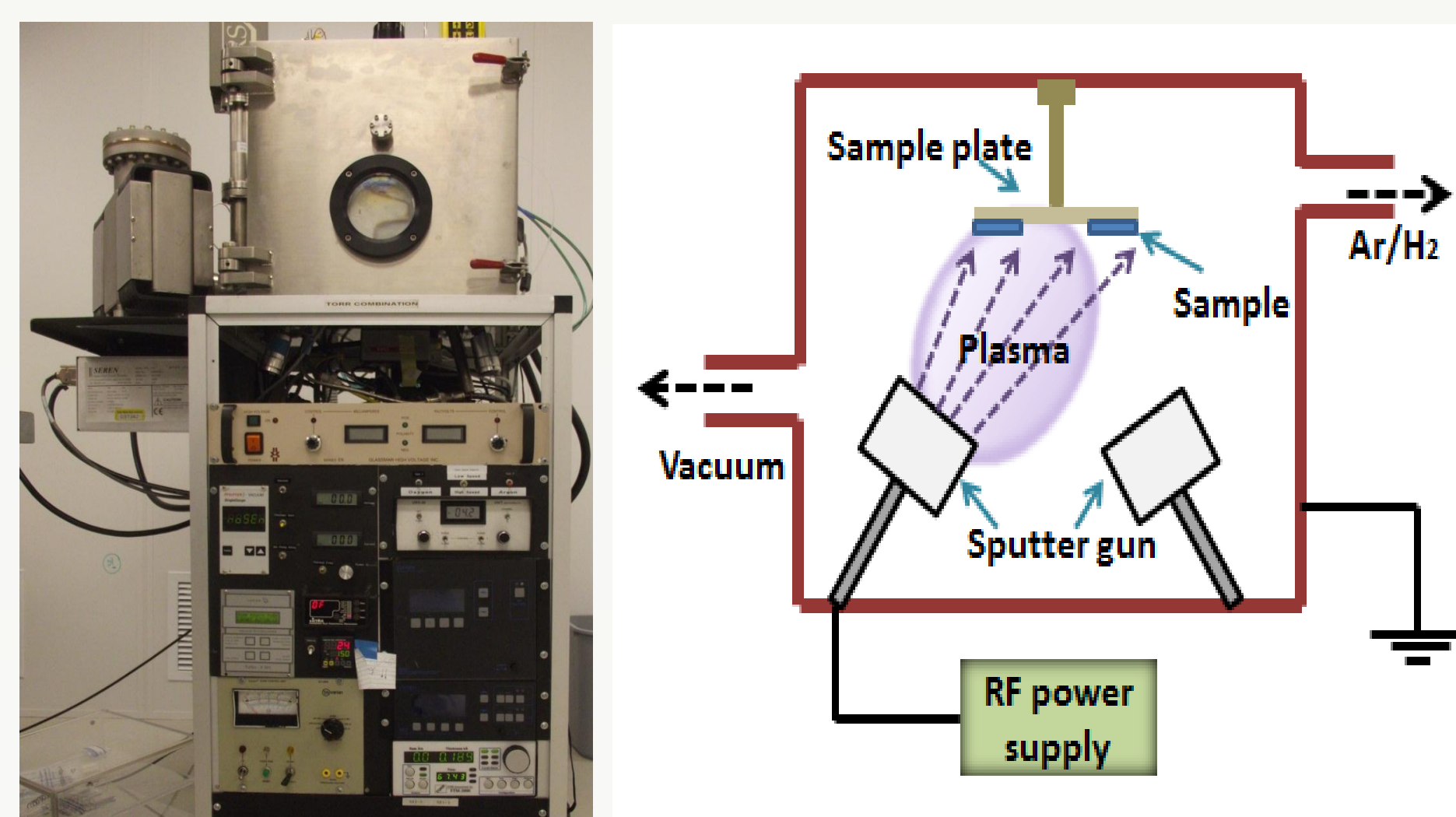
Background

- Hydrogenated nanocrystalline silicon (nc-Si:H) is a mixed phase material of sub-nanometer scaled Si crystallites embedded in an amorphous matrix [1].
- Nc-Si:H thin films are a well-accepted material for cost-effective and flexible photovoltaics due to its easy and low-cost fabrication
- Nc-Si:H is more resilient against Light – Induced Degradation (LID) compared to its amorphous silicon counterparts [2].
- Difficulties in explaining LID in nc-Si:H
 - complex microstructure consisting of nanometer size grains and amorphous grain boundaries [3]
 - lack of experimental tools that can probe local electronic properties in sub-nanometer dimension

Objectives

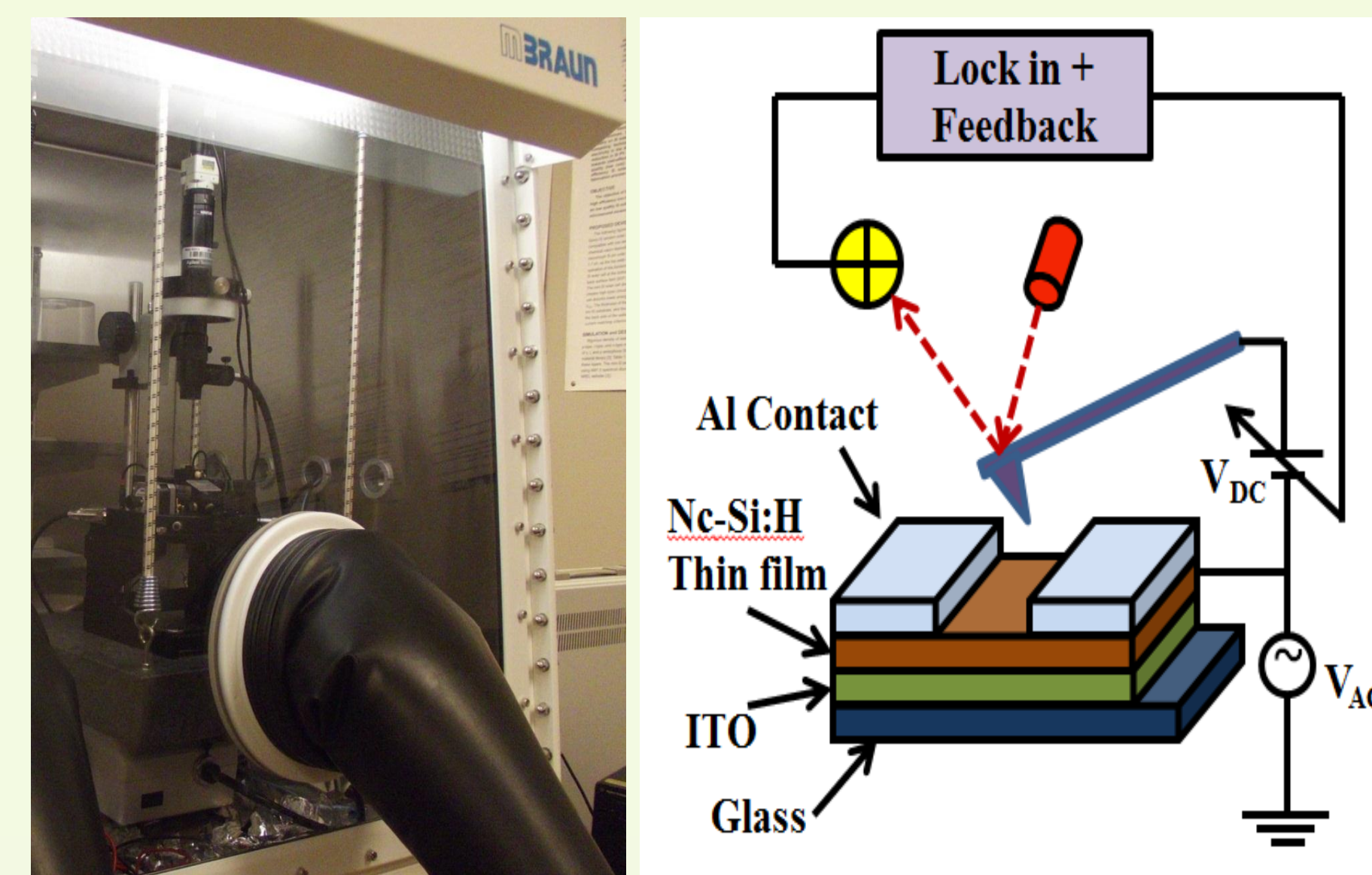
- Use EFM as a nanoprobe for local characterization of nc-Si:H thin films
- Study LID and its effect on local electronic properties, such as charge distribution at grains and GBs
- Probe qualitatively the change in charge distribution before and after LID
- Correlate film microstructure with local charge distribution from AFM and EFM measurements

Procedure – Sputtering



- Thin films deposition:**
 - Rf magnetron sputtering deposition
 - Undoped crystalline silicon target
 - H₂/Ar atmosphere - H₂:Ar was 33:67
 - Temperature - 200 °C
 - Process pressure 10.4 mTorr
 - Plasma power 250 W
 - Substrate to target distance 15 cm
 - Film thickness 95 nm

Procedure – AFM and EFM



- Thin films characterization:**
 - Intermittent contact mode AFM using Agilent 5500 SPM Nanoscope
 - Budget sensors AFM tip
 - Pt/Ir coating, 25 nm diameter, 40 N/m force constant, 75 kHz resonance frequency
 - Tip bias from -3V to +3V
 - White LED of 100mW/cm² power density

Results – EFM images

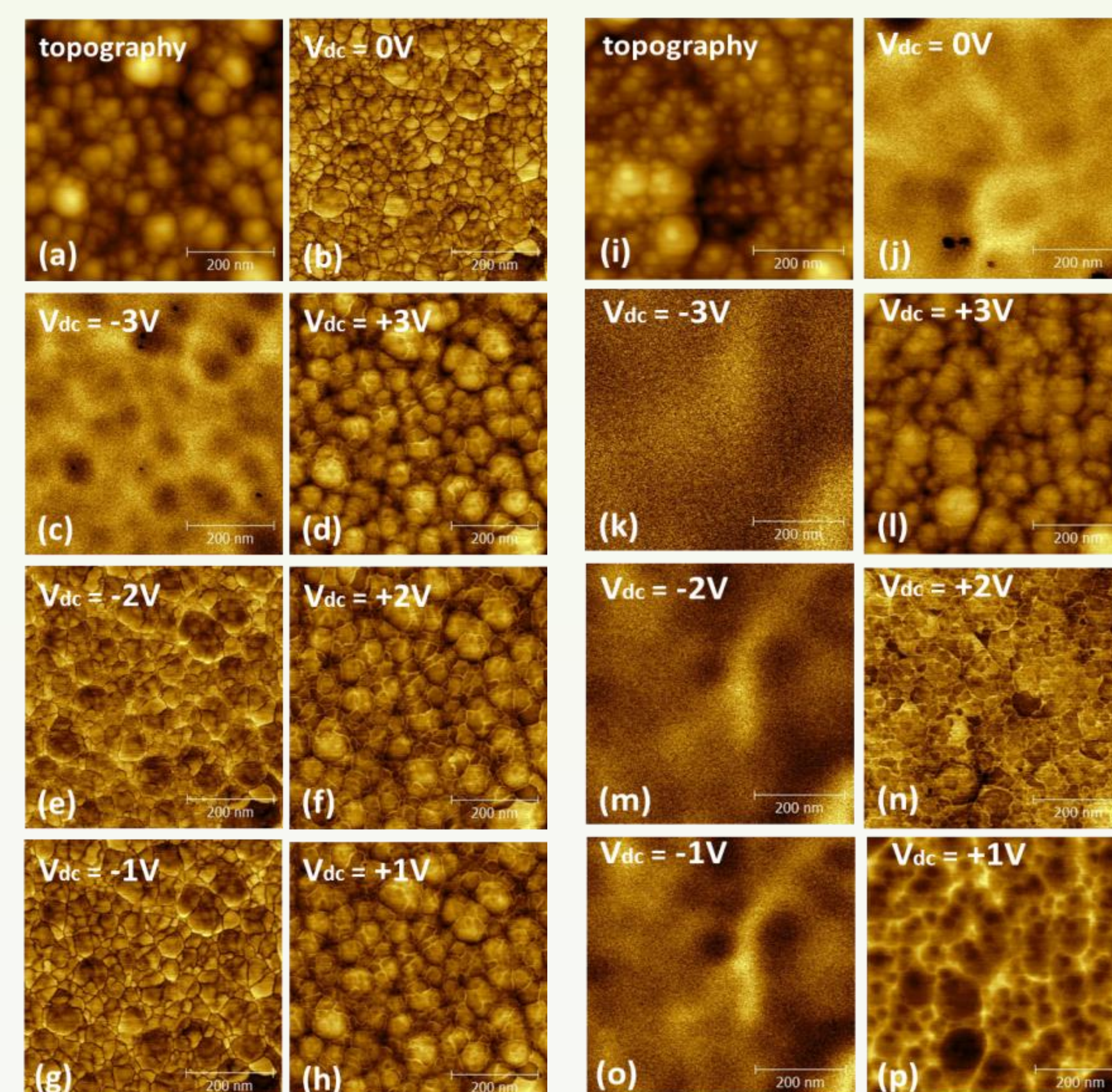
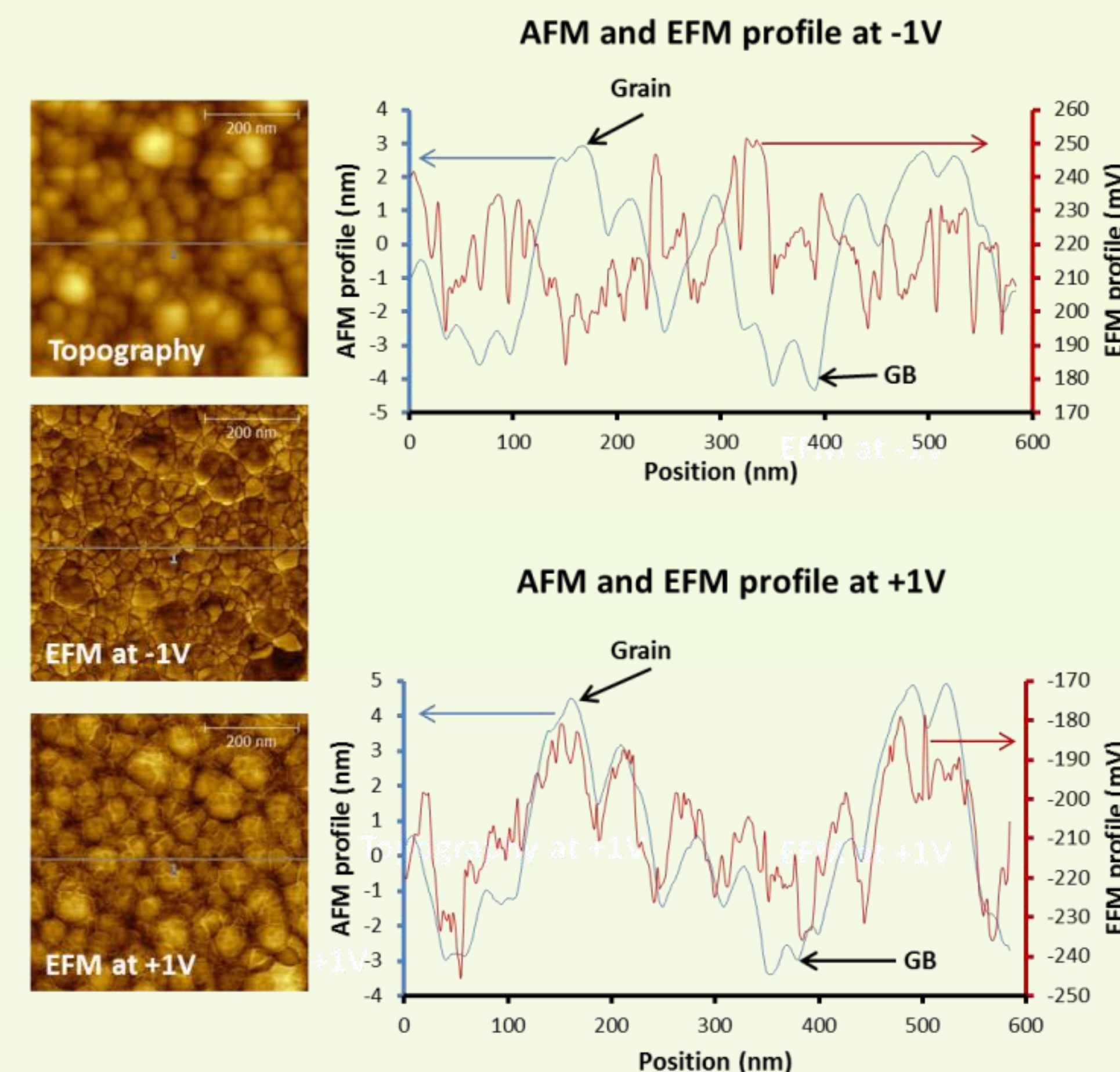


Figure 1. Topography and EFM before illumination

Figure 2. Topography and EFM after illumination

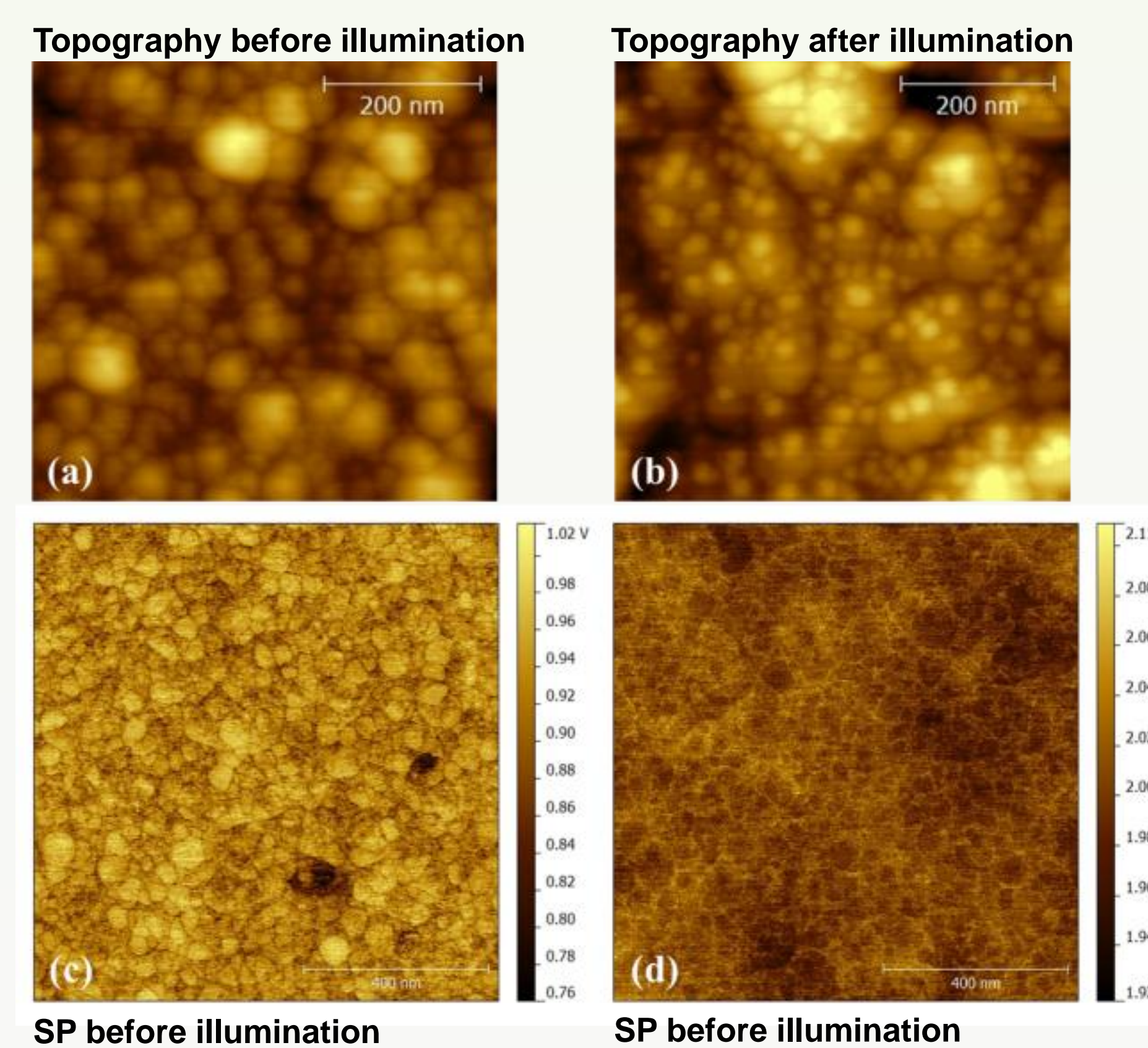
- Darker regions are at lower potential and brighter regions are at higher potential
- Change in polarity in bias voltage reverses the polarity of the surface potential indicating dominance of negative type of charge accumulation.
- Concentration of negative charges at GBs increase after LID with increasing tip-bias voltage
- Active potential barriers at large GBs is observed

Results – line profiles



- EFM offers higher spatial resolution demonstrated by potential variation at GBs between two small individual grains
- Negative correlation at negative bias; positive correlation at positive bias between 'geometric' (AFM) and 'electronic' (EFM) grains
- Modulation in the surface potential within the interior of grains, size of grains, grain clusters and GBs

Results – AFM and SP



- Topography:**
 - Grainy surface
 - Small individual grains and large grain clusters are separated by distinct GBs
 - Each grain cluster contains ~10 – 20 smaller grains
 - LID evolved small blister-like structures throughout the surface

Results – AFM and SP

- KFM images:**
 - The density of GB increases after LID
 - Photo generated charges result in band bending at GBs
 - Newly formed blisters behave as small grains with defective and disordered GBs.

Conclusion

- Combined AFM and EFM/ KFM were used to observe the formation of active potential barrier and photo-induced charge accumulation at grains and GBs.
- Negative type of defects was found to dominate in the material whose density increased after LID
- The change in charge distribution was more pronounced near large GBs suggesting the large GBs to create metastable trap states
- EFM was demonstrated as a powerful tool for qualitative measurement of surface potential and sign of accumulated charges
- The results are in good agreement with the established theoretical models reported in the literatures.

References

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